

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Hayashi et al.
Appl. No. : 10/565,696
Filed : January 24, 2006
For: : RESIN FOR RESIST, POSITIVE
RESIST COMPOSITION, AND
METHOD OF FORMING RESIST
PATTERN
Examiner : Huhn, R.
Group Art Unit : 4131

SUBMISSION WITH RCE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **March 2, 2009**, please amend the above-referenced application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.